

Session Title:	[TC2] Plasma Etch Measurements & Diagnostics II
Session Date:	November 15 (Tue.), 2022
Session Time:	11:20-12:40
Session Room:	Room C (Grand Ballroom 2, 2F)
Session Chair:	Prof. Bert Ellingboe (Dublin City Univ., Ireland)

[TC2-1] [Invited] 11:20-11:50

Data-Informed Advanced Plasma Equipment/Process Control Technologies for Etch Process
Yeong-Geun Yook, Jong-Sik Kim, Dae-Chul Kim, Yong-Hyun Kim, Young-Woo Kim, and Jung-Sik Yoon (KFE, Korea)

[TC2-2] [Invited] 11:50-12:20

Plasma Diagnostic-Based Semiconductor Process Simulation
Jae-Hyeong Park (Jeonbuk Nat'l Univ., Korea), Won-Seok Chang (KFE, Korea), Hae-Sung You (Jeonbuk Nat'l Univ., Korea), Deuk-Chul Kwon, JungSik Yoon (KFE, Korea), and Yeon-Ho Im (Jeonbuk Nat'l Univ., Korea)

[TC2-3] 12:20-12:40

A Study on Plasma Potential and Ion Energy Control Method Using Resonant Passive Antenna
Minsu Choi, Sijun Kim, Inho Seong, Chulhee Cho, Youngseok Lee, Wonnyoung Jeong, Yebin You, Byeongyeop Choi, and Shinjae You (Chungnam Nat'l Univ., Korea)